

### Amendment to the Claims

This listing of claims will replace all prior versions, and listing of claims in the application:

#### Listing of Claims

1. (currently amended): A process for ~~preparing or~~ selecting a composition or product yielding a maximum fragrance burst of one or more of the fragrance components of at least 20% and for providing enhanced deposition of one or more fragrance components onto surfaces on which said composition or product comes into contact, when said composition is diluted relative to an undiluted product, wherein said composition is defined by perfume burst index PBI:

$$\text{PBI} = \frac{\phi - 1.4/\text{CMC}}{K}$$

wherein  $\phi$  = oil/water partition coefficient of a selected perfume or perfume components in a mixture;

CMC = critical micellization concentration (wt./wt.) of selected surfactant systems or mixture of surfactant systems in diluent or continuous phase;  
K = volatility constant of selected perfume from said continuous phase or diluent atmospheres);

wherein said process comprises (1) selecting a perfume or at least one component of said a first perfume mixture and; (2) selecting a first surfactant system or mixture of surfactants systems; and (3) formulating said perfume or component of said first perfume mixture and said first surfactant system or mixture of surfactant systems to form said

composition or product such that the above noted variables are calculated to provide a PBI that is greater than about 3;

wherein by maximum fragrance burst of at least 20% is meant that the perfume concentration in the headspace above said fragrance or fragrance components increases at least 20% when it is diluted relative to the perfume concentration in the headspace ~~of an undiluted product comprising the same fragrance or fragrance components of a second composition differing in perfume properties, surfactant concentration and/or CMC of a surfactant system with a PBI less than that of the first composition, both compositions~~ measured as the compositions comprising said fragrance or fragrance components ~~is~~ are diluted below the critical micelle concentration (CMC) of the fragrance, surfactant and water system.

2. (currently amended): A process according to claim 1, wherein said first perfume is a type 2 perfume selected to have an oil/water partition coefficient greater than about 500 and volatility constant of less than about 20.
3. (currently amended): A process according to claim 2, wherein said first perfume is selected from the group consisting of allyl cyclohexane propionate, ambrettolide, Ambrox DL (dodecahydro-3a,6,6,9a-tetramethyl-naphtho[2,1-b]furan), amyl benzoate, amyl cinnamate, amyl cinnamic aldehyde, amyl salicylate, anethol, aurantiol, benzophenone, benzyl butyrate, benzyl iso-valerate, benzyl salicylate, cadinene, campylcyclohexal, cedrol, cedryl acetate, cinnamyl cinnamate, citronellyl acetate, citronellyl isobutyrate, citronellyl propionate, cuminic aldehyde, cyclohexylsalicylate, cyclamen aldehyde, cyclomyral, dihydro isojamonnate,

diphenyl methane, diphenyl oxide, dodecanal, dodecalactone, ethylene brassylate, ethylmethyl phenylglycidate, ethyl undecylenate, exaltolide, Galoxilide™ (1,3,4,6,7,8-hexhydro,4,6,6,7,8,8-hexamethyl-cyclopenta-γ-2-benzopyran), geranyl acetate, geranyl isobutyrate, hexadecanolide, hexenyl salicylate, hexyl cinnamic aldehyde, hexyl salicylate, α-ionone, β-ionone, (-ionone, α-irone, isobutyl benzoate, isobutyl quinoline, Iso E Super™ (7-acetyl,1,2,3,4,5,6,7,8-octahydro,1,1,6,7-tetramethyl naphthalene), cis-jasmone, lilial, linalyl benzoate, 20 methoxy naphthaline, methyl cinnamate, methyl eugenol, (-methylionone, methyl linolate, methyl linolenate, musk indanone, musk ketone, musk tibetine, myristicin, neryl acetate, δ-nonolactone, (-nonolactone, patchouli alcohol, phantolide, phenylethyl benzoate, phenylethylphenylacetate, phenyl heptanol, phenyl hexanol, α-santalol, thibetolide, tonalid, δ-undecalactone, (-undecalactone, vertenex, vetiveryl acetate, yara-yara, ylangene, and mixtures thereof.

4. (currently amended): A process according to claim 1, wherein said first perfume is a type 3 perfume selected to have a partition coefficient of greater than about 500 and volatility constant of about 20 to about 1000.
5. (currently amended): A process according to claim 4, wherein said first perfume is selected from the group consisting of allo-ocimene, allyl caproate, allyl heptoate, anisole, camphene, carvacrol, carvone, citral, citronellal, citronellol, citronellyl nitrile, coumarin, cyclohexyl ethylacetate, p-cymene, decanal, dihydromyrcenol, dihydromyrcenyl acetate, dimethyl octanol, ethyllinalool, ethylhexyl ketone, eucalyptol, fenchyl acetate, geraniol, gernyl formate, hexenyl isobutyrate, hexyl acetate, hexyl neopentanoate, heptanal, isobornyl acetate, isoeugenol, isomenthone, isononyl acetate, isononyl alcohol, isomenthol, isopulegol, limonene, linalool, linalyl acetate, menthyl acetate, methyl chavicol, methyl octyl

acetaldehyde, myrcene, naphthalene, nerol, neral, nonanal, 2-nonanone, nonyl acetate, octanol, octanal,  $\alpha$ -pinene,  $\beta$ -pinene, rose oxide,  $\alpha$ -terpinene,  $\gamma$ -terpinene,  $\alpha$ -terpinenol, terpinolene, terpinyl acetate, tetrahydrolinalool, tetrahydromyrcenol, undecenal, veratrol, verdox, and mixtures thereof.

6. (currently amended): A process for ~~preparing~~ selecting a composition according to claim 1 yielding maximum fragrance burst of at least 25%.
7. (canceled)
8. (canceled)
9. (currently amended): A process according to claim 1, wherein said first surfactant system and/or surfactant system mixtures are selected to have a CMC greater than about .0001 wt. to wt.
10. (currently amended): A process according to claim 9, wherein ~~the~~ said first surfactant systems contain surfactants selected from the group consisting of sodium lauryl ether sulfate, sodium laurate, potassium laurate, sodium oleate, potassium oleate, triethanolamine laurate, alkylpolyglucosides, sodium lauryl sulfate, caprylamidopropyl betaine, sodium cocoylisethionate and mixtures thereof.

11. (currently amended): A process according to claim 9, wherein said first surfactant systems or surfactant system mixtures includes CMC modifying ingredients selected from the group consisting of urea; glycerine; C<sub>1</sub>-C<sub>12</sub> straight-chained or branched alcohols or diols; water soluble polymers selected from polyvinylpyrrolidone, polyvinylalcohol, polyethyleneglycol, polypropyleneglycol and mixtures thereof; multivalent electrolytes selected from magnesium, calcium, aluminum salts and mixtures thereof; and sugars selected from dextrose, glucose, maltose, galactose; sucrose and mixtures thereof.